



IFV

Attorney Docket No. 0524-0140.01

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application of: )  
)  
Osamu NOZAWA, et al. )  
)  
Serial No.: 10/667,823 )  
)  
Filed: September 22, 2003 )  
)  
For: PHASE SHIFT MASK BLANK, )  
PHOTO MASK BLANK, AND )  
MANUFACTURING APPARATUS )  
AND METHOD OF BLANKS )  
)  
Art Unit: 1756 )  
)  
Examiner: Mohamedulla, Saleha )

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Shannon Wallace  
Date: April 13, 2005

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**ELECTION AND AMENDMENT A**

Sir:

In response to the Restriction Requirement of  
March 22, 2005, Applicant hereby elects Group II: Claims  
15-22, in the above-identified application. In addition,  
please amend the above-identified application as follows: